

IN THE CLAIMS

Claims 1-12 (canceled)

13. (new) A substrate coating comprising a transparent Si_3N_4 or SiN_x layer directly on a substrate, a semimetallic layer above the Si_3N_4 or SiN_x layer and with a further Si_3N_4 or SiN_x layer as well as with a dielectric oxide layer selected from the group consisting of Al_2O_3 , SnO , TiO_2 and SiO_2 , wherein the dielectric oxide layer is disposed on the semimetallic layer and the further Si_3N_4 layer on the dielectric oxide layer.

14. (new) The substrate coating as claimed in claim 13, wherein the semimetallic layer comprises a CrN layer.

15. (new) The substrate coating as claimed in claim 13, wherein a dielectric oxide layer is provided between the transparent Si_3N_4 or SiN_x layer directly on the substrate and the semimetallic layer.

16. (new) The substrate coating as claimed in claim 13, wherein x is a number smaller than $4/3$.

17. (new) The substrate coating as claimed in claim 14, wherein the semimetallic layer comprises NiCrN or NiCrO_x .

18. (new) A substrate coating as claimed in claim 13, wherein the transparent Si_3N_4 or substoichiometric SiN_x layers have each a layer thickness of 20 to 120 nm.

19. (new) A substrate coating as claimed in claim 13, wherein the dielectric oxide layers have each a layer thickness of 4 to 120 nm.

20. (new) A substrate coating as claimed in claim 13, wherein the semimetallic NiCrN, CrN or NiCrO_x layers have a layer thickness of 5 to 40 nm.

21. (new) A substrate coating as claimed in claim 13, wherein said substrate is glass.

22. (new) Substrate coating as claimed in claim 13, wherein said substrate is a synthetic material.

23. (new) A substrate coating as claimed in claim 13, further comprising additional layers comprising of Cr, Ni or NiCr.

24. (new) A substrate coating as claimed in claim 13, wherein the dielectric oxide layer is comprises Nb₂O₅.